Supporting Information

## Topological Insulator-Based van der Waals Heterostructures for Effective Control of Massless and Massive Dirac Fermions

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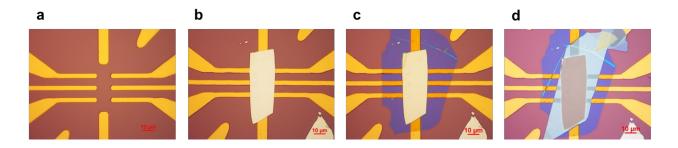
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**Figure S1 Device fabrication process.** (a) The gold contact electrodes in Hall bar geometry were fabricated using a standard electron beam lithography on a SiO<sub>2</sub> (300 nm) coated Si substrate. (b) A BSTS flake exfoliated from the single crystal BSTS was transferred onto the pre-patterned electrodes using a home-built micro-manipulation stage. (c) A hBN flake exfoliated from a single crystal hBN was then transferred on the BSTS. (d) A graphite flake was transferred on the hBN at about 95°C with the heating on the Si substrate, and joined to a gate electrode.

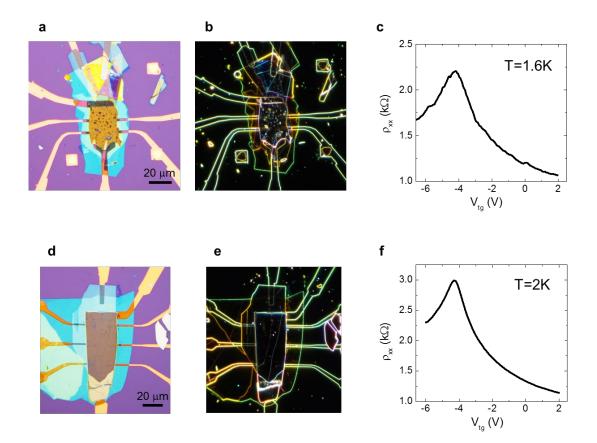


Figure S2 Effect of heterostructure interfaces on the transport properties. The representative (a, d) bright-field, and (b, e) dark-field optical images of a BSTS/hBN/graphite heterostructure with the graphite layer transferred at (room temperature, 95°C heating). The blisters formation at the hBN-graphite interface is prevented by the high temperature (close to the vaporization of water) transfer. The (c, f) four-probe resistivities ( $\rho_{xx}$ ) as a function of gate-voltage applied through the graphite gate-electrode for the BSTS (with, without) blisters forming at the hBN-graphite interface. With the same thickness of hBN (28 nm) layer, the sharper  $\rho_{xx}$  peak in (f) is attributed to the cleaner interface of the vdW heterostructure layers, resulting in a higher gating efficiency through the hBN/graphite gate.

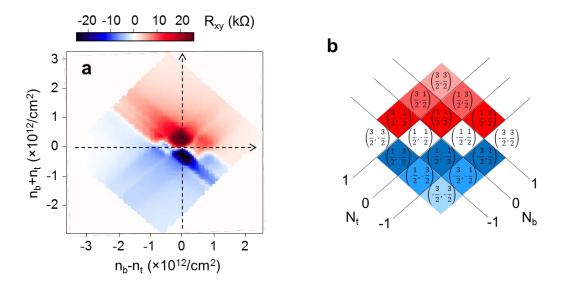


Figure S3 Quantization of Hall resistance from top and bottom surface states. (a) 2D color map of the Hall resistance ( $R_{xy}$ ) as a function of sum and difference of the charge densities of the top ( $n_t$ ) and bottom ( $n_b$ ) surfaces. The vertical and horizontal dashed line arrows cross the symmetric and antisymmetric Landau Level filling factors between top ( $v_t$ ) and bottom ( $v_b$ ) surface states. (b) The quantization in  $R_{xy}$  is illustrated by a Landau level filling color schematic for the top and bottom surface states. The ( $v_t$ ,  $v_b$ ) of the corresponding Landau level indices of the top ( $N_t$ ) and bottom ( $N_b$ ) surface states are labeled in (b).

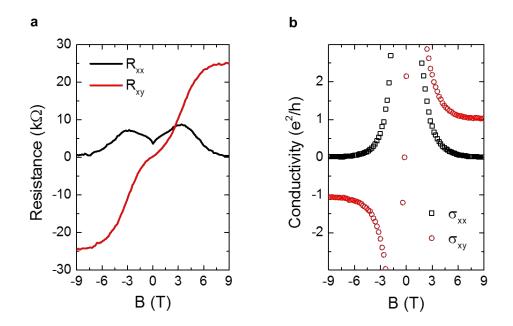


Figure S4 Magnetic field dependent QHE. (a)  $R_{xx} \& R_{xy}$ , and (b)  $\sigma_{xx} \& \sigma_{xy}$  as a function of magnetic field for the BSTS/hBN/graphite device. The  $R_{xx}$  ( $\sigma_{xx}$ ) and  $R_{xy}$  ( $\sigma_{xy}$ ) are highly-symmetrical and antisymmetrical, respectively, in opposite magnetic field. The  $\sigma_{xy}$  approaches quantum limit of e<sup>2</sup>/h (-e<sup>2</sup>/h), together with the vanishing in  $\sigma_{xx}$ , at magnetic field greater than 6T (-6T).

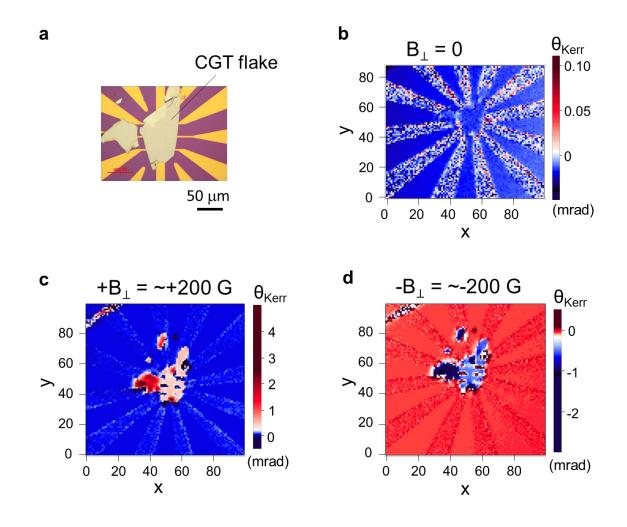


Figure S5 Kerr rotation studies of a  $Cr_2Ge_2Te_6$  (CGT) flake. The magnetic properties of a 80 nm thick CGT flake (a) were studied using a Sagnac interferometer at cryogenic temperature. 2D spatial mapping of Kerr rotation angles ( $\theta_{Kerr}$ ) for the CGT device measured at (b) 0 G, (c) ~+200 G and (d) ~-200 G out of plane magnetic field. The large  $\theta_{Kerr}$  detected and the antisymmetrical of  $\theta_{Kerr}$  in opposite magnetic field confirm its ferromagnetic behavior.

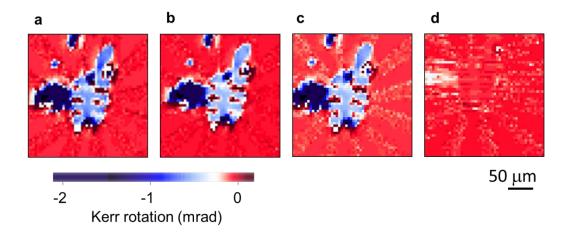


Figure S6 Temperature dependent Kerr rotation of a CGT flake. 2D maps of Kerr rotation angle ( $\theta_{Kerr}$ ) of the 80 nm CGT device measured at different temperature of (a) 4.7 K, (b) 20 K, (c) 60 K and (d) 80 K. The vanishing of  $\theta_{Kerr}$  at 80 K indicates that the ferromagnetic phase transition occurred at a temperature between 60 to 80 K.

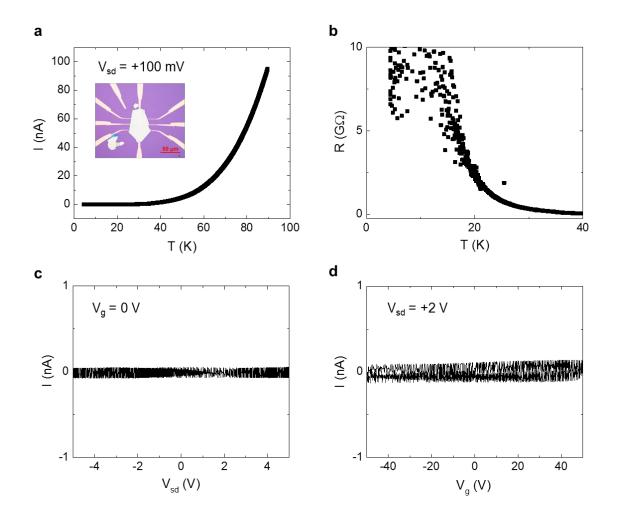
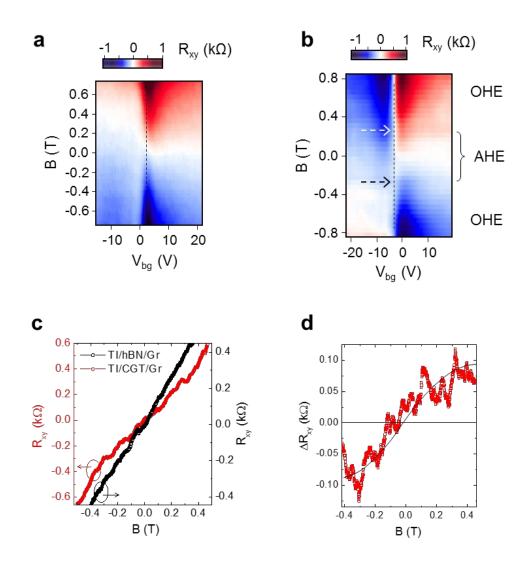


Figure S7 Transport properties of a single crystal  $Cr_2Ge_2Te_6$  (CGT) flake. (a) Sourcedrain current (I) of a 120 nm CGT device (shown in the inset) as a function of temperature, measured at a fixed source-drain voltage of +100 mV. (b) The resistance (R) of the CGT device as a function of temperature shows the insulating behavior with R exceeding 2 GΩ at temperature below 20 K. (c) The source-drain I versus V of the CGT device measured at temperature of 4 K. No source-drain I detected in the range of V<sub>sd</sub> applied (±5V), showing the truly insulating of the CGT at cryogenic temperature. (d) The source-drain I as a function of gate voltage (V<sub>g</sub>) applied through the Si/SiO<sub>2</sub> gate. No source-drain I

detected indicates that the CGT is in the electronic band gap region within the range of  $V_g$  applied.



**Figure S8 Anomalous Hall effect of a BSTS/CGT/Gr device.** Color maps of the Hall resistance  $(R_{xy})$  of the (a) BSTS/hBN/Gr, and (b) BSTS/CGT/Gr devices as a function of magnetic field and backgate voltage. The ordinary Hall effect (OHE) and anomalous Hall effect (AHE) regions were labeled in the figure. (c) Comparison of the  $R_{xy}$  at low magnetic field (±0.5 T) for the BSTS/hBN/Gr and BSTS/CGT/Gr devices. The different slope of  $R_{xy}$  vs B in BSTS/CGT/Gr device plot at low magnetic field range of about ±0.3 T is a result of the AHE. (d) The difference

between  $R_{xy}$  of BSTS/hBN/Gr and BSTS/CGT/Gr ( $\Delta R_{xy}$ ) as a function of magnetic field. The black curve is a guide to the eyes to show the antisymetrical of  $\Delta R_{xy}$  in the opposite magnetic field.

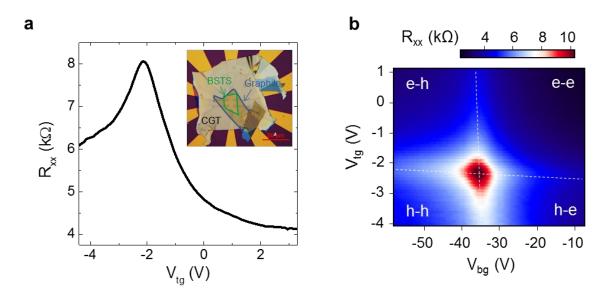


Figure S9 Gate-dependent resistance of a BSTS/CGT/Gr device. (a) Four-probe resistance ( $R_{xx}$ ) of the BSTS as a function of  $V_{tg}$  applied through a CGT dielectric (thickness ~250 nm) measured at temperature of 1.6 K. Inset in (a) is the optical images of the device. (b) Color plot of the  $R_{xx}$  of the BSTS as a function of dual-gate voltages with the topgate as CGT/graphite and backgate as SiO<sub>2</sub>/Si. Similar to the BSTS/hBN/Gr device, the top and bottom surface states can be tuned into the four quadrant conductions as labeled in (b).

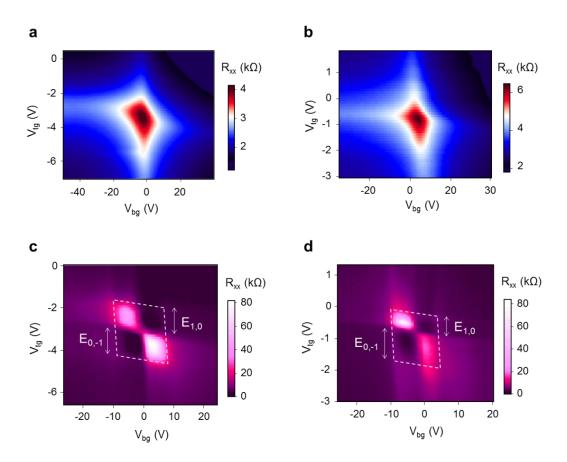
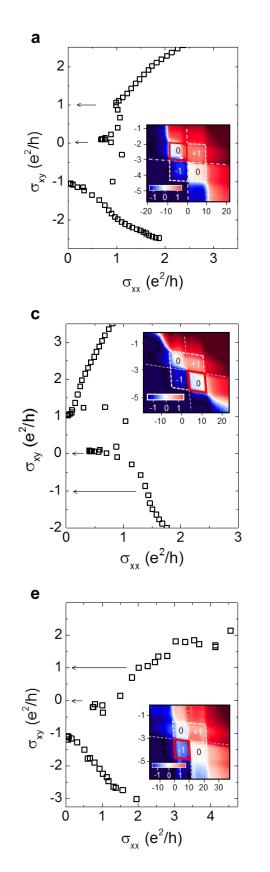
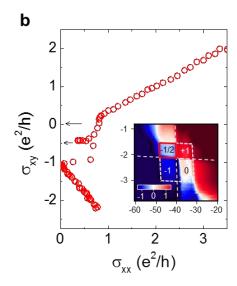
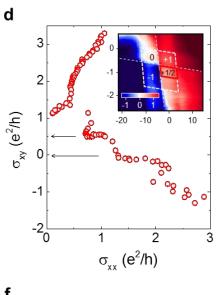


Figure S10 Estimation of the magnetic gap from dual-gated transport. Dual-gated color maps of longitudinal resistance (R<sub>xx</sub>) for (a, c) BSTS/hBN/Gr\_2, and (b, d) BSTS/CGT/Gr\_2 devices measured at magnetic field of 0 and 9T. The thickness of the hBN and CGT layers are about 20 nm and 200 nm, respectively. Different from the hBN/Gr gating, the top surface tuned by CGT/Gr shows an irregular LL spacing between N<sub>t</sub>=-1 to 0 and N<sub>t</sub>=0 to +1. The magnetic exchange gap induced by the 2D ferromagnet CGT is evaluated from the difference between the  $E_{0,-1}$  and  $E_{1,0}$ LL spacing. The  $E_{1,0}$  is calculated from the LL energy,  $E_1 - E_0 = \sqrt{2e\hbar v_F^2B} \approx 34.8$  meV, where the Fermi velocity ( $v_F$ ) is ~3.2×10<sup>5</sup> m/s. The  $E_{0,-1}$  is expressed as  $E_{0,-1} = E_{-1} - E_0 + \Delta$ , where  $E_{-1} = E_1$  and  $\Delta$  is the magnetic exchange gap. The  $\Delta$  is estimated to be about 18 meV.







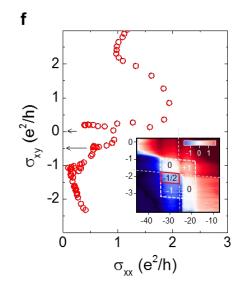


Figure S11 Renormalization group flow plots for various BSTS devices. The  $\sigma_{xy}$  versus  $\sigma_{xx}$  plots for three BSTS/hBN/Gr devices (a) BSTS/hBN/Gr\_1, (c) BSTS/hBN/Gr\_2, and (e) BSTS/hBN/Gr\_3, and three BSTS/CGT/Gr devices (b) BSTS/CGT/Gr\_1, (d) BSTS/CGT/Gr\_2, and (f) BSTS/CGT/Gr\_3, measured at 9T. Thickness of hBN and CGT are in the range of 18-23 nm and 200-300 nm, respectively. The dual-gated  $\sigma_{xy}$  color maps of the respective devices are inserted in the figures. The BSTS/hBN/Gr devices all show regular spaced integer quantum Hall plateaus developed near the center Dirac point. In comparison, the BSTS/CGT/Gr devices display the irregular quantum Hall plateaus with the extended v= -1 compared to v= +1 plateaus. The half-integer quantization plateau are consistently observed near or in the magnetic gap region in all the CGT-coupled BSTS devices. The renormalization group flow plots in (b), (d) and (f) all show half-integer -<sup>1</sup>/<sub>2</sub> (or +<sup>1</sup>/<sub>2</sub>) features developed between v= -1 (or +1) and 0.

Table S1. Device specifications of the BSTS/hBN/Gr and BSTS/CGT/Gr devices. The
thicknesses of the BSTS ( $d_{BSTS}$ ), top gate dielectric layers of hBN ( $d_{hBN}$ ) or CGT ( $d_{CGT}$ ) flakes
are measured using a Bruker Dimension Icon atomic force microscopy.

Device label	d <sub>BSTS</sub> (nm)	d <sub>hBN</sub> (nm)	d <sub>CGT</sub> (nm)
BSTS/hBN/Gr_1	100	18	-
BSTS/hBN/Gr_2	61	16	-
BSTS/hBN/Gr_3	105	22	-
BSTS/hBN/Gr_4	80	18	-
BSTS/hBN/Gr_5	120	17	-
BSTS/hBN/Gr_6	135	20	-
BSTS/CGT/Gr_1	112	-	160
BSTS/CGT/Gr_2	68	-	130
BSTS/CGT/Gr_3	120	-	200